IN THE SPECIFICATION:

Please amend the specification as follows:

<u>Page 7, lines 9-14 (the brief description for Figures 3-5)</u>: please replace these paragraphs with the following rewritten paragraphs:

Figure 3 illustrate illustrates a block diagram depicting a developed photoresist being exposed to an ultraviolet (UV) light in accordance with one embodiment of the invention.

Figure 4 illustrates a block diagram depicting an etched substrate having a post-etched hardened top layer of a silicon-containing photoresist.

Figure 5 illustrate illustrates a flowchart depicting a method for increasing a silicon-containing photoresist selectivity in accordance with one embodiment of the invention.